



Session Title:	[TuD1] Advanced Lithography I
Session Date:	November 12 (Tue.), 2024
Session Time:	13:00-14:45
Session Room:	Room D (Sidney Room, 2F, Paradise Hotel Busan)
Session Chair:	Dr. Youssef Drissi (imec, Belgium)

[TuD1-1] [Plenary] 13:00-13:45

Next-Generation Semiconductor Manufacturing: Role of EUV Lithography and Advanced Process Development

Sandip Halder (imec, Belgium)

[TuD1-2] [Invited] 13:45-14:15

The Challenges of EUVL Patterning and Discussion about the Technology to Prepare for Next Generation Devices

Woo Jin Jung, Seongbo Shim, and Chan Hwang (Samsung Electronics Co., Ltd., Korea)

[TuD1-3] [Invited] 14:15-14:45

Integrating Actinic EUV Metrology with Advanced Analytical Technologies

Sangsul Lee (POSTECH, Korea)